

In re Appln. of Sachiko HATTORI  
Application No. Unassigned

*ABSTRACT AMENDMENTS*

Replace the Abstract with:

A resist film is applied ~~onto~~ to an entire surface and subjected to patterning substantially in the same form as an opening to bury the resist film inside the opening. ~~Where~~ When a positive resist is used, a photomask having a light-shielding portion ~~whose region is~~ with an area smaller than the opening is used, ~~or where~~ in patterning. When a negative resist is used, a photomask having a light transmitting portion ~~whose region is~~ with an area smaller than the opening is used.